

Title (en)  
VACUUM COATING SYSTEM AND METHOD FOR OPERATING A VACUUM COATING SYSTEM

Title (de)  
VAKUUMBESCHICHTUNGSANLAGE UND VERFAHREN ZUM BETRIEB EINER VAKUUMBESCHICHTUNGSANLAGE

Title (fr)  
INSTALLATION DE REVÊTEMENT SOUS VIDE ET PROCÉDÉ POUR FAIRE FONCTIONNER UNE INSTALLATION DE REVÊTEMENT SOUS VIDE

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Application  
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Abstract (en)  
[origin: WO2010078860A1] The invention relates to a vacuum coating system (01), comprising at least one process chamber (02) that can be evacuated and at least one entry opening (10) and at least one exit opening (11), wherein wafer elements (03), which are coated in the process chamber (02) while passing through, can be fed into and removed from the process chamber through the entry opening (10) and the exit opening (11), and wherein a paddle valve (08, 09), which can be moved between an open position and a pressure-tight closed position along a paddle valve closing path, is provided on the entry opening (10) and the exit opening (11), and wherein for the purpose of transporting the wafer elements (03) a transport system having at least three transport devices (04, 05, 06, 17) is provided, wherein the first transport device (04, 17) is arranged upstream of the entry opening (10), wherein the second transport device (05, 17) is arranged in the process chamber (02), and wherein the third transport device (06, 17) is arranged downstream of the exit opening (11), and wherein each transport device (04, 05, 06, 17) comprises at least one revolving transport element (14, 18) on which the wafer elements (03) can be placed from above and delivered through the vacuum coating system (01) by revolvingly driving the transport elements (14, 18), wherein the transport system has an adjustable transfer transport device (12, 13, 16) at the entry opening (10) and/or at the exit opening (11), said transfer transport device being adjustable between a transfer position and an idle position, wherein in the transfer position of the transfer transport device (12, 13, 16) the wafer elements (03) can be transferred from one transport device (04, 05, 06, 17) to the next transport device downstream in the delivery direction (7) through the open exit opening or through the open entry opening, and wherein in the idle position of the transfer transport device (12, 13, 16) the entry opening (10) and/or the exit opening (11) can be opened or closed by adjusting the associated paddle valve (08, 09) along the paddle valve closing path.

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